

Figure 1. GPC of the SiO₂ PEALD as a function of HMDMS feeding time.

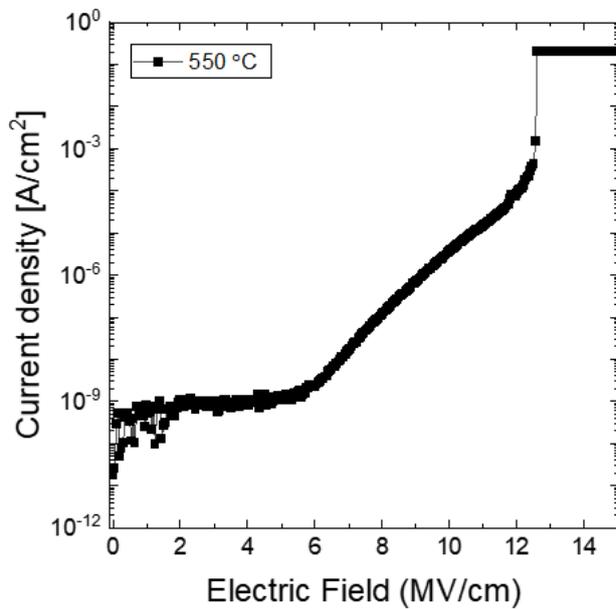


Figure 2. The leakage current density versus electric field plot of 20-nm-thick PEALD SiO₂ film.

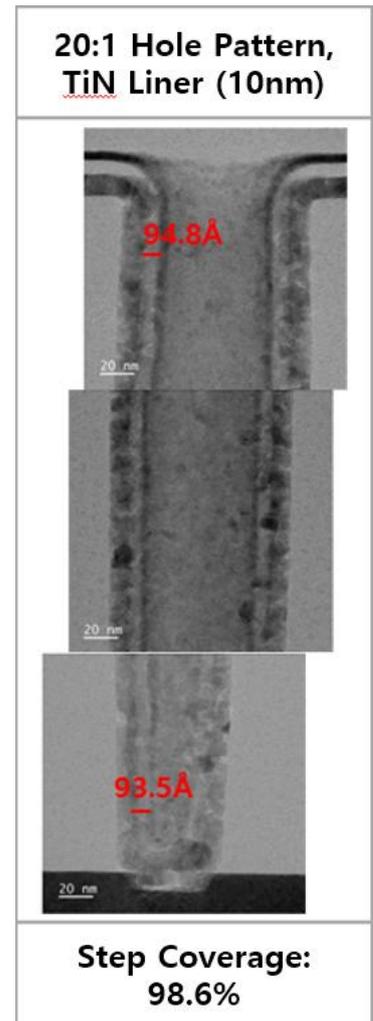


Figure 3. Step coverage of 10-nm-thick SiO₂ PEALD on 20:1 hole patterns.

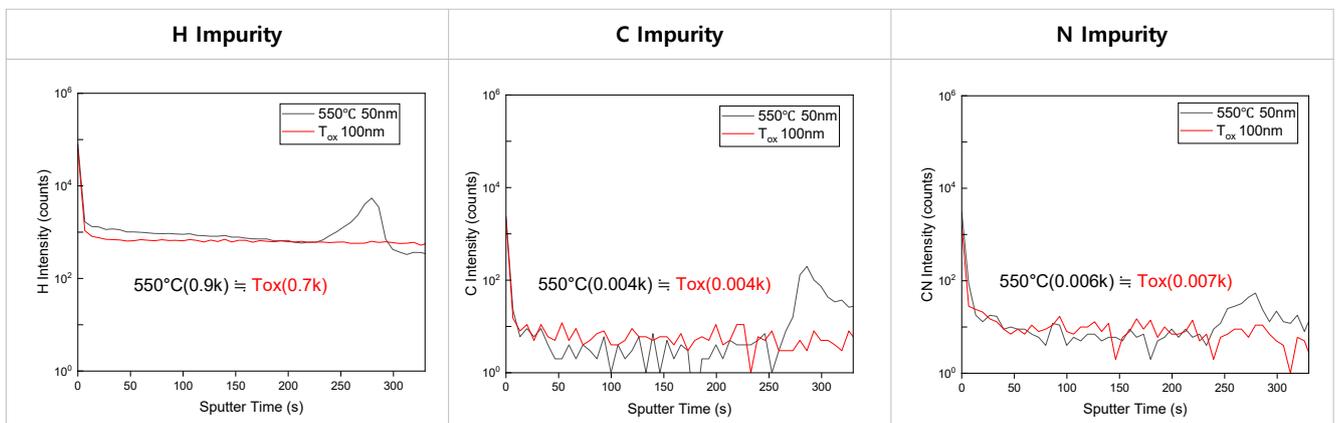


Figure 4. H, C, and N impurity levels of the SiO₂ PEALD film and a thermally grown oxide film by SIMS.